

CLAIMS

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- 2 1. A microelectromechanical apparatus comprising:  
3      a base;  
4      a flap having a portion coupled to the base so that the  
5      flap is movable out of the plane of the base from a first  
6      angular orientation to a second angular orientation;  
7      wherein the base has an opening that receives the flap  
8      when the flap is in the second angular orientation, the  
9      opening having one or more sidewalls, wherein at least one  
10     of the sidewalls contacts a portion of the flap such that  
11     the flap assumes an orientation substantially parallel to  
12     that of the sidewall when the flap is in the second  
13     angular orientation; and  
14     a sidewall electrode disposed in one or more of the  
15     sidewalls.
  
- 1 2. The microelectromechanical apparatus of claim 1 wherein  
2      the flap further comprises a magnetically active element.
  
- 1 3. The microelectromechanical apparatus of claim 2 wherein  
2      the magnetically active element is a magnetic material.
  
- 1 4. The microelectromechanical apparatus of claim 2 wherein  
2      the magnetically active element is a coil.
  
- 1 5. The microelectromechanical apparatus of claim 2 further  
2      comprising an external magnet.
  
- 1 6. The apparatus of claim 1 wherein the flap is connected to  
2      the base by one or more flexures.
  
- 1 7. The apparatus of claim 7 wherein at least one flexure is  
2      electrically conductive.

- 1        8. The microelectromechanical apparatus of claim 1 further  
2                comprising a light-deflecting element disposed on the  
3                flap.
- 1        9. The microelectromechanical apparatus of claim 1, wherein  
2                the sidewall electrode is electrically isolated from the  
3                base.
- 1        10. The microelectromechanical apparatus of claim 1 further  
2                comprising:  
3                a voltage source coupled between the flap and the sidewall  
4                electrode to apply an electrostatic force between the  
5                sidewall electrode and the flap.
- 1        11. The apparatus of claim 10 wherein the flap contains a  
2                magnetically active material and the electrostatic force  
3                between the sidewall electrode and the flap is sufficient  
4                to prevent the flap from changing position in the presence  
5                of an applied magnetic field.
- 1        12. The apparatus of claim 1 further comprising:  
2                an electrode disposed on the base; and  
3                a voltage source coupled between the electrode in the base  
4                and the flap to apply an electrostatic force between the  
5                electrode in the base and the flap.
- 1        13. The apparatus of claims 1 where the base is made from a  
2                substrate portion of an SOI (silicon-on-insulator) wafer  
3                and the flap is defined from a device layer portion of the  
4                SOI wafer.
- 1        14. The apparatus of claim 1 wherein the one or more  
2                flexures include one or more torsional beams.

- 1        15. The apparatus of claim 1, further comprising one or  
2                  more conductive landing pads disposed on an underside of  
3                  the flap wherein the one or more conductive landing pads  
4                  are electrically isolated from the flap.
- 1        16. The apparatus of claim 15, wherein one or more of the  
2                  conductive landing pads are electrically coupled to a  
3                  sidewall electrode.
- 1        17. The apparatus of claim 15 wherein one or more of the  
2                  conductive landing pads is electrically coupled to the  
3                  base.
- 1        18. The apparatus of claim 1 wherein the sidewall includes  
2                  a sidewall electrode and one or more conductive landing  
3                  pads that are electrically isolated from the sidewall  
4                  electrode.
- 1        19. The apparatus of claim 18 wherein one or more of the  
2                  landing pads are electrically coupled to the flap.
- 1        20. The apparatus of claim 18 wherein the sidewall  
2                  electrode is electrically isolated from the base.
- 1        21. An array of one or more structures, wherein each structure  
2                  comprises:  
3                  a base;  
4                  a flap having a portion coupled to the base so that the  
5                  flap is movable out of the plane of the base from a first  
6                  angular orientation to a second angular orientation, the  
7                  flap containing a reflecting element;  
8                  wherein the base has an opening with largely vertical  
9                  sidewalls, at least one of the sidewalls containing an  
10                 electrode, wherein the sidewalls contact a portion of the

11 flap such that the flap assumes an orientation  
12 substantially parallel to that of the sidewall when the  
13 flap is in the second angular orientation.

1 22. An array of claim 21 wherein one or more of the  
2 structures includes a sidewall electrode disposed in  
3 one or more of the sidewalls.

1 23. The array of claim 21, wherein the sidewall electrode  
2 is electrically isolated from the base.

1 24. An array of claim 21 wherein the array forms an optical  
2 switch.

1 25. An apparatus comprising:

2 a flap that is movable from a first angular orientation to  
3 a second angular orientation; and  
4 a magnetic material disposed on the flap, the magnetic  
5 material having a stepped pattern.

1 26. A method for reducing stiction in a MEMS device having a  
2 flap that is movable with respect to a base, the method  
3 comprising:  
4 applying a fixed force to the flap to move the flap at  
5 least partially out of contact with an underlying base.  
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